

<b>Notice of References Cited</b>	Application/Control No. 10/673,583		Applicant(s)/Patent Under Reexamination MITROVIC, ANDREJ S.	
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*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	"Emerging Paradigms in Semiconductor Manufacturing"; Paul P. Castrucci; 1990 Int'l Semiconductor Mfg. Science Symposium; IEEE 1990
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	X	"Detailed Simulation for Semiconductor Manufacturing"; Robert W. Atherton et al; Proceedings of the 1990 Winter Simulation Conference

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.

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